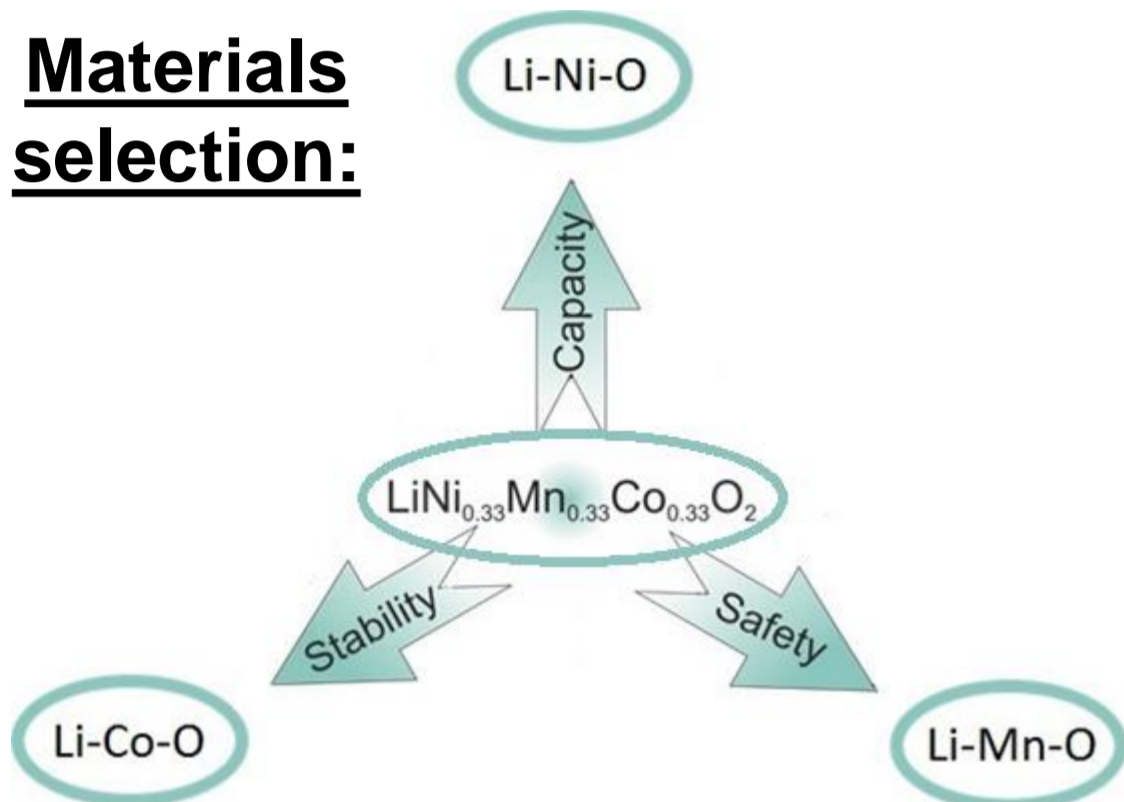


Constitution and microstructure of Li-Ni-Mn-Co-O thin film cathodes

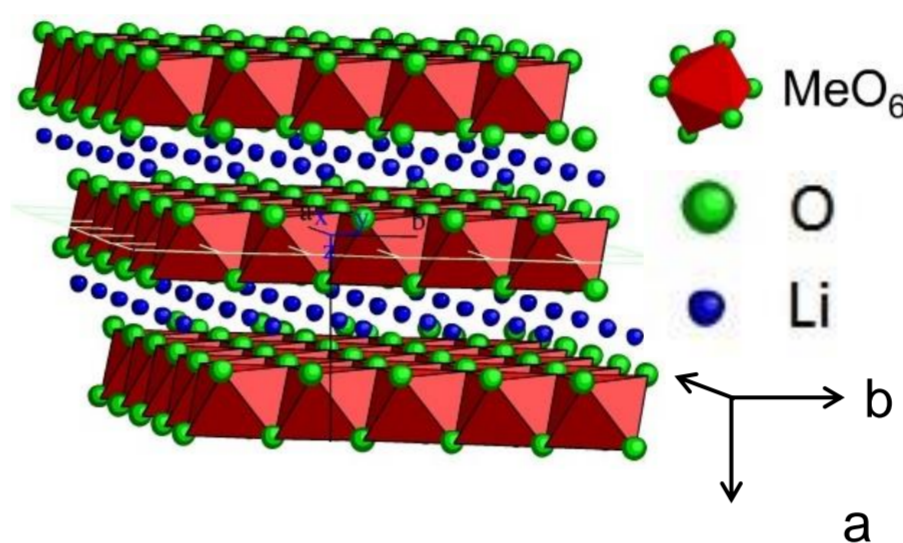
1.5 μm thick Li-Ni-Mn-Co-O cathodes have been deposited by r.f. magnetron sputtering from $\text{Li}_{1.25}(\text{Ni}_{0.42}\text{Mn}_{0.21}\text{Co}_{0.37})\text{O}_2$ target. The elemental composition varies with argon working gas pressure (0.2 Pa to 20 Pa) and was determined by inductively coupled plasma-optical emission spectroscopy (ICP-OES) in combination with carrier gas hot extraction. The microstructure of the films was characterized by X-ray diffraction (XRD) and by micro-Raman spectroscopy at room temperature. The as-deposited films are nanocrystalline and show their highest grade of crystallinity in the range between 0.2 Pa to 0.5 Pa and at 7 Pa. Correlations between process parameter, constitution and microstructure are discussed in detail.

Materials selection:



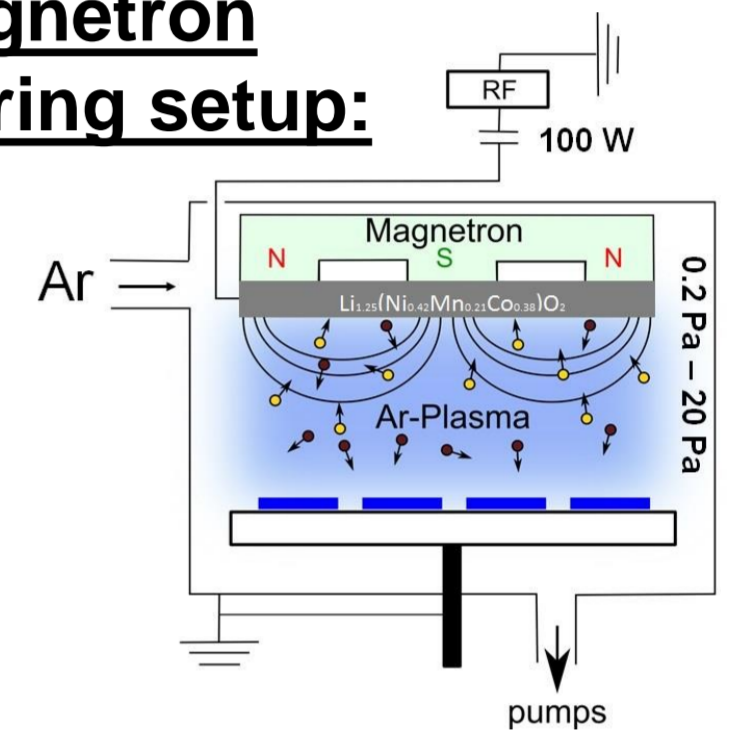
Properties and structure of $\text{Li}(\text{Ni}_{1/3}\text{Mn}_{1/3}\text{Co}_{1/3})\text{O}_2$:

- **Theoretical capacity:** 290 mAh/g
- **Practical capacity:** 160-180 mAh/g
- **Voltage vs. Li:** 2.5 V - 4.6 V
- **Space group:** R3m
hexagonal lattice
 $a = b = 2.867\text{\AA}$ $c = 14.246\text{\AA}$
 $\alpha = \beta = 90^\circ$ $\gamma = 120^\circ$
- **Color:** black-grey



Prof. Dr. B. Scrosati, online lecture, Helmholtz Institute Ulm, 2013

Magnetron sputtering setup:

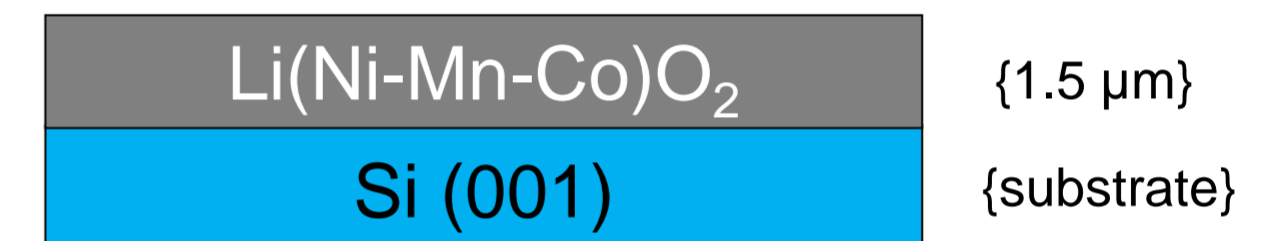


Deposition parameters:

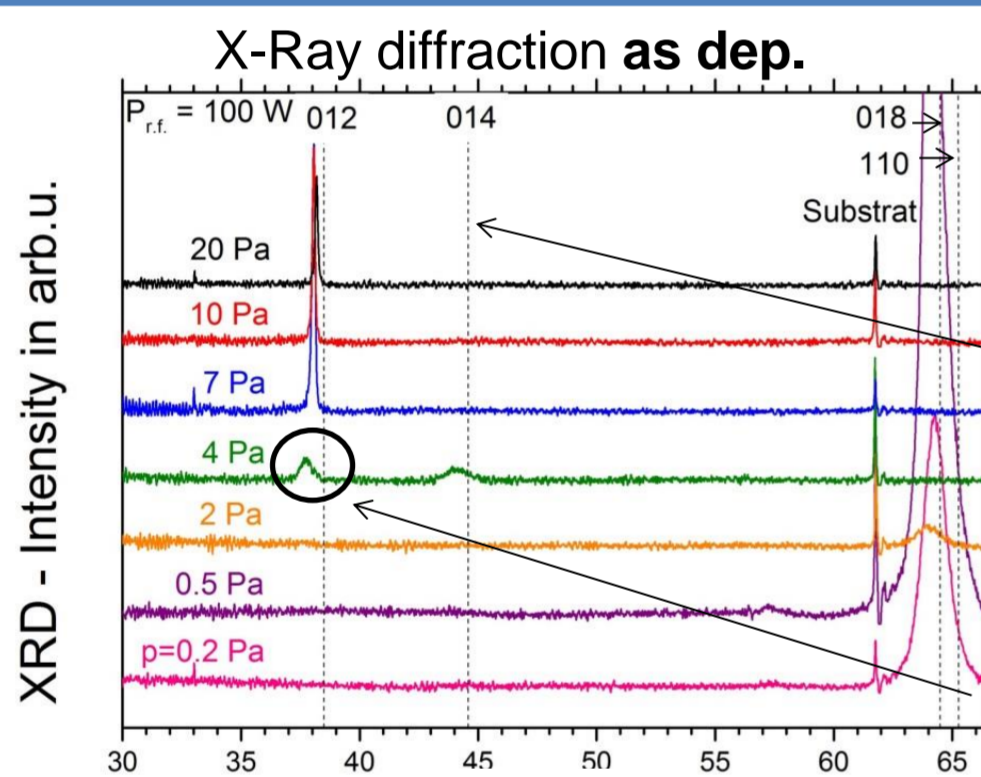
Argon working gas pressure: 0.2 Pa to 20 Pa / target power: 100 W
film thickness: $\sim 1.5\ \mu\text{m}$

Annealing parameters:

300 $^\circ\text{C}$ / 600 $^\circ\text{C}$, 1 hour, 10 Pa Ar/ O_2 (80:20)-atmosphere

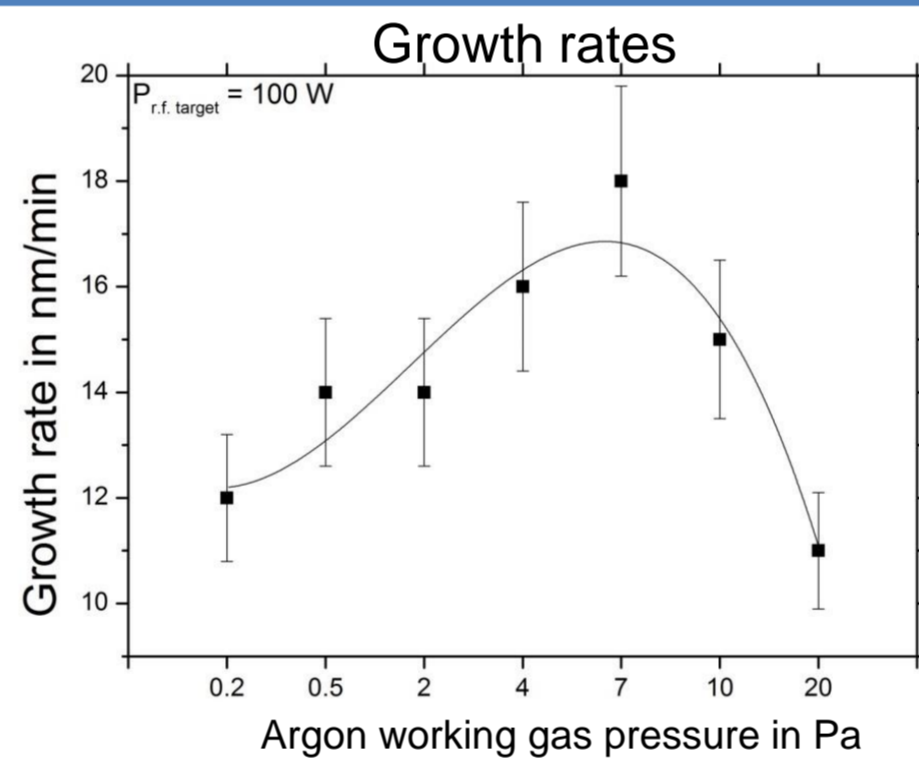


Results:

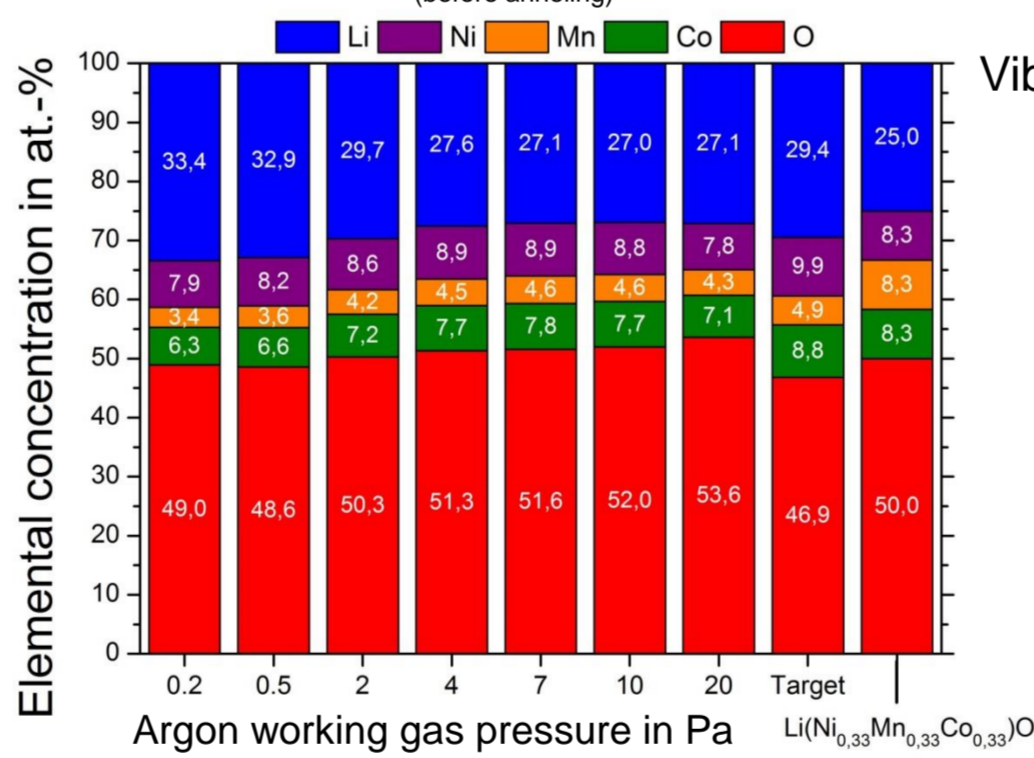


Dashed lines show reflection position reported in literature

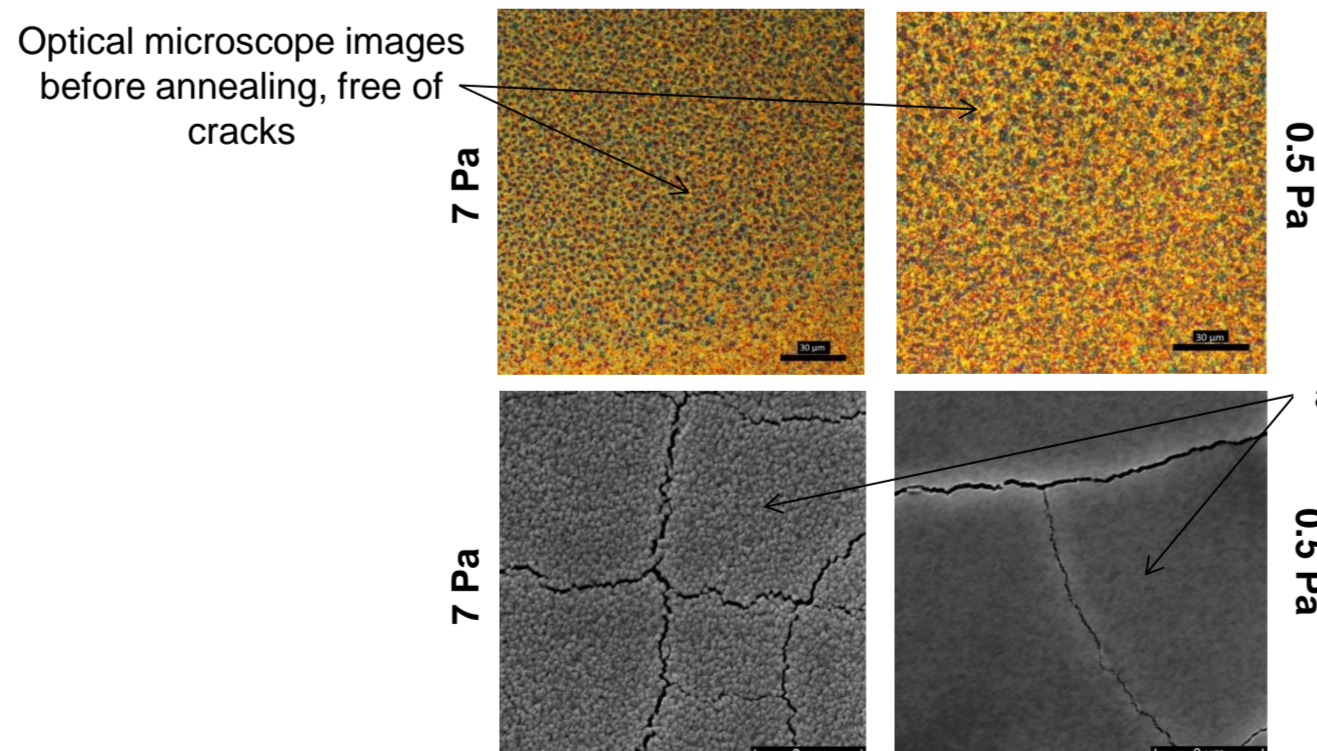
Deviation of peak positions and literature value



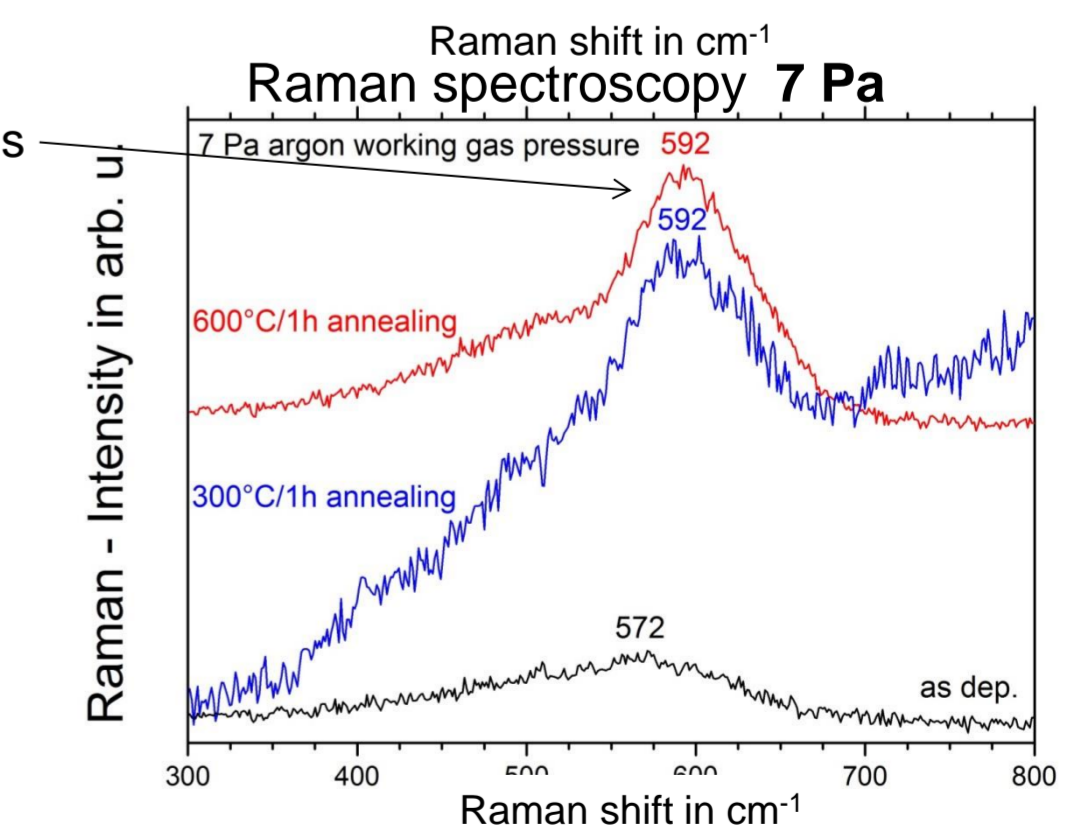
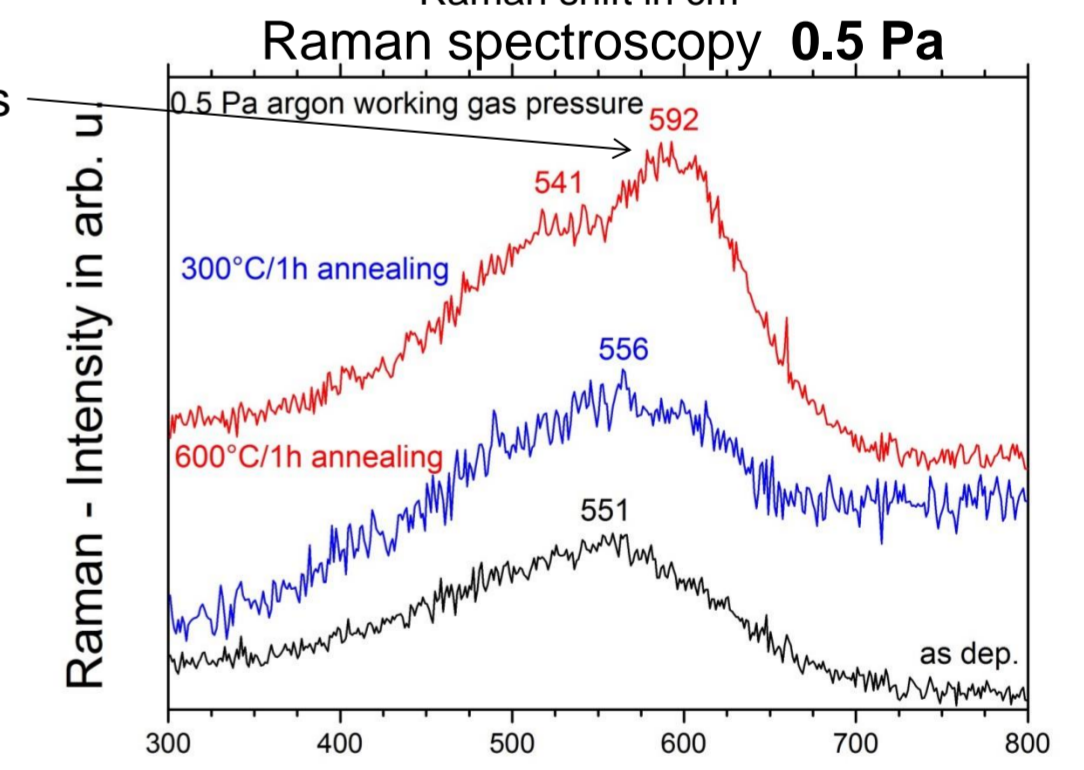
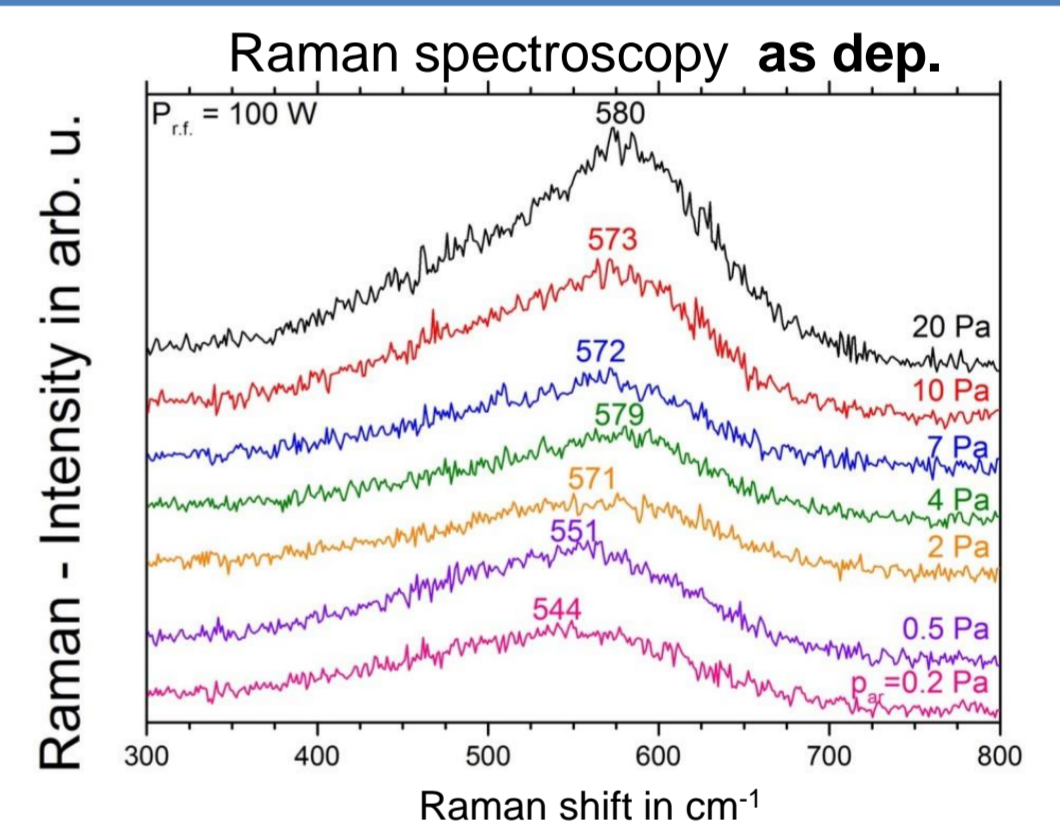
ICP-OES and CGHE analysis (before annealing)



Surface images



A_{1g} mode
Vibration of O Atoms in LiMO_2



Conclusions and Outlook:

- Li-Ni-Mn-Co-O thin films were synthesised with different microstructures and elemental compositions.
 - The X-Ray reflections deviate from positions reported in literature. The difference is probably caused by residual stresses or different elemental composition.
 - At 0.5 Pa and 7 Pa the as deposited films show the highest grade of crystallinity.
- Next steps will be annealing in different atmospheres, investigations of the electrochemical behavior, surface modifications with laser and plasma technology, development of an artificial SEI.

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Principal investigators:

S. Ulrich, H. J. Seifert, KIT (IAM-AWP)

Additional investigators:

M. Strafela, J. Fischer, M. Rinke, T. Bergfeldt, KIT (IAM-AWP)